What is claimed is:

1. A self-aligned fabrication process for a nozzle plate of an inkjet print head, comprising the steps of:

providing a substrate having at least one activated device thereon;

forming a first film on the substrate;

forming a second film on the first film;

defining the second film to form a convex portion corresponding to the activated device, exposing a part of the surface of the first film;

forming a third film on the exposed surface of the first film, covering the convex portion;

removing the third film on the convex portion; and

etching the convex portion and the first film under the convex portion to form a via.

2. The self-aligned fabrication process for a nozzle plate of an inkjet print head as claimed in claim 1, wherein the substrate is a silicon substrate.

3. The self-aligned fabrication process for a nozzle plate of an inkjet print head as claimed in claim 1, wherein the third film is made of spin-on-glass.

4. The self-aligned fabrication process for a nozzle plate of an inkjet print head as claimed in claim 1, wherein the third film on the convex portion is removed by etching to expose the surface of the convex portion.

5. The self-aligned fabrication process for a nozzle plate of an inkjet print head as claimed in claim 1, wherein the third film on the convex portion is removed by photolithography.

6. The self-aligned fabrication process for a nozzle plate of an inkjet print head as claimed in claim 1, wherein the via is formed by plasma dry etching.

7. The self-aligned fabrication process for a nozzle plate of an inkjet print head as claimed in claim 6, wherein the plasma dry etching uses oxygen as the main etching gas.

8. The self-aligned fabrication process for a nozzle plate of an inkjet print head as claimed in claim 1, wherein the first film is a polymer film.

9. The self-aligned fabrication process for a nozzle plate of an inkjet print head as claimed in claim 1, wherein the second film is a polymer film.

10. The self-aligned fabrication process for a nozzle plate of an inkjet print head as claimed in claim 1, wherein the activated device is a thin-film heater.

11. A self-aligned fabrication process for a nozzle plate of an inkjet print head, comprising the steps of:

providing a silicon substrate having at least one activated device thereon;

forming a first film on the substrate;

forming a second film on the first film;

defining the second film to form a convex portion corresponding to the activated device, exposing a part of the surface of the first film;

forming a spin-on-glass film on the exposed surface of the first film, covering the convex portion;

removing the spin-on-glass film on the convex portion; and

etching the convex portion and the first film under the convex portion to form a via.

12. The self-aligned fabrication process for a nozzle plate of an inkjet print head as claimed in claim 11, wherein the spin-on-glass film on the convex portion is removed by etching to expose the surface of the convex portion.

13. The self-aligned fabrication process for a nozzle plate of an inkjet print head as claimed in claim 11, wherein the spin-on-glass film on the convex portion is removed by photolithography.

14. The self-aligned fabrication process for a nozzle plate of an inkjet print head as claimed in claim 11, wherein the via is formed by plasma dry etching.

15. The self-aligned fabrication process for a nozzle plate of an inkjet print head as claimed in claim 14, wherein the plasma dry etching uses oxygen as the main etching gas.

16. The self-aligned fabrication process for a nozzle plate of an inkjet print head as claimed in claim 11, wherein the first film is a polymer film.

17. The self-aligned fabrication process for a nozzle plate of an inkjet print head as claimed in claim 11, wherein the second film is a polymer film.

18. The self-aligned fabrication process for a nozzle plate of an inkjet print head as claimed in claim 11, wherein the activated device is a thin-film heater.